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10-29-01
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of:

Mamoru NAKASUJI, et al.

0300 \$
ATTN: Box Missing Parts

Serial No.: **09/891,611**

Group Art Unit: **Unknown**

Filed: **June 27, 2001**

Examiner: **Unknown**

For: **INSPECTION SYSTEM BY CHARGED PARTICLE BEAM AND METHOD OF
MANUFACTURING DEVICES USING THE SYSTEM**

AMENDMENT TRANSMITTAL

Commissioner for Patents
Washington, D.C. 20231

October 22, 2001

Sir:

Transmitted herewith is an Amendment in the above-identified application.

The fee has been calculated as shown below:

	CLAIMS AS AMENDED					
	Claims Remaining After Amendment	Highest Number Previously Paid For		Present Extra	Large Entity	Additional Fee
Total Claims	164	20	=	144	X \$18	\$ 2,592.00
Independent Claims	45	3	=	42	X \$84	\$ 3,528.00
XX First Presentation of Multiple Dependent Claims					\$280	\$ 280.00
TOTAL FEES ENCLOSED:						\$ 6,400.00

☒ Enclosed please find our check in the amount of \$ 6,400.00 for the additional claims fee in connection with this amendment. The Commissioner is hereby authorized to charge payment for any additional fees associated with this communication or credit any overpayment to Deposit Account No. 01-2340. Two duplicates of this sheet are attached.

Respectfully submitted,

ARMSTRONG, WESTERMAN, HATTORI
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10/24/2001 SDIRETA1 00000083 09891611

01 FC:103 2592.00 OP
02 FC:102 3528.00 OP
03 FC:104 280.00 OP

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Date: October 22, 2001

Sir:

Prior to calculation of the filing fee and examination of this application, please amend the
above-identified application as follows:

IN THE CLAIMS:

Please amend claims 53, 55, 75 and 81 as follows:

a¹
53. (Amended) The inspection apparatus of claim 51 or 52 wherein the apparatus
is constructed so that an energizing condition of an objective lens is obtained under a state where
a pattern on a wafer is electrically charged.

a²
55. (Amended) A method for manufacturing semiconductor devices wherein a wafer
during a manufacturing process or after processing is evaluated by using the inspection apparatus
of any one of claims 51, 52 or 54.